ASSIGNMENT-1

That out the semiconductor products and its corresponding

And Company

i) TSMC (Tauson Semuonductors manufacturing Company)

ii) NVIDIA Corporation

(ii) Advanced Mura Devues (AMD)

iv) Intel Corporation

V) Qualionm Inverporated

vi) Samsung Electronics

Vi) Texas Instruments

Product

service for manufacturing semiconductors.

GPUs, Processors, A I and Deep Learning hordware

CPU, GPUL, SOC

microprocessor, SSD,

FPGA, Gaphics software

Mobile processor, GPU,

Modern,

Memory (DRAM, Flosh)
Processors, I mage sensors

Analog IC, DSP,

2) What are the tatest laptop processors from AMD, Intel and Apple: Frequency and node

Ans i Intel

19-14900K on 19 14th gen

Clock Speed: upto 6.0 GHZ

Process node: 10 nm or Intel 7

ii) AMD

Rygen 9 7950×30 Clock speed : 455.7 GHZ

Process role: 5 mm mm

iii) Apple

M3 Max Clock speed: - upto 4.05 GHZ Process node: - 3nm

3) What are the latest mobile processors available from Qualcomm and riedutele: Frequency and node

Ans qualionm:

Snapdragon Gen 3 clock Speed: 3-36 Hz

Process node: 4 nm

Mediatek :-

Dimensity 9300 Clock speed: 3.25 GHZ Process rade: 4nm 4) What are the different job rules available in VISI field.

Ans i) VLSI Design Enginees

- ii) Verification Enginees
- iii) Physical Design Enginees
- in) ASIC Design Enginees
- V) FPGA Design Enginees
- Vi) Design Automation Enginees
- Vii) Analog/Mixed Signal design Engineer

VIII) (AD Enginees

ix) soc sribilect

x) RF Design Engineer

5) Why there is a shift from BJT-MOSFET-FINFET in detail.

Ane Reasons why there was a shift from BJT to MOSFET:

i) Power Efficiency: - MOSFETS consume less powers compared to BJT, because they have a very high imput impedance and draw negligible input when in a state state.

- 11) Ministure MOSFETs allow for ease ministuryation of devices due to their simples structure and compatibility with IC pabrication processes.
- MOSFETS, became popular por its love power Consumption, making it a standard choice for digital IC.

Playons for shift from MOSFET to FINFET.

- i) Leabage (werent: As transister suger decreased, leabage swirent became engrysteant concern in MOSFET, Fin FET, with their 3D structure help thus usual by providing better control over current.
- scaling of transister dimensions, allowing for the continuation of Moore's lane. It provides better performance and energy officiency.
- slope shoracteristics, which means they can swetch between on and off states more effectively reducing powers consumption during swetching

- 6) E volution of memory technology
- Ans 1) Vacuum Tuber and Oday lines:
 - · Early computers used vacuum tubers memory storage. There were large, power-hungry, and had limited capacity.
 - · Delay lines were also used involving delay of anothic waves through a medium to refresent benong data.
 - 2) Magnetic Core memory
 - rings to store bits, providing faster and more reliable data storage
 - 3) DRAM (Dynamic Random Aues Memory)
 - stored in 1960s, DRAM relies on the charge stored in capacitore to represent bits. Its widely used due to the higher density compared to other.
 - 4) SRAM (Static RAM)
 - "SRAM, introduced around same time as ORAM uses flip flops to store bute. It is faster than ORAM but costlies and lower derisity

- 5) Flash Memory or NAND memory
 - "Flash memory; introduced in 1980s, resolutionized non-vollatile storage. It is used in USB derives, memory cards and SSDS. Flash memory stores data in ploating gate transistors.
- 6) SORAM (Synchronous Dynamic RAM)
 - nemory operations with clock speed of CPU providing paster data rates compared to DRAM.
- DOR SDRAM, starting with DDR in early 2000; improved data transfer rates by transferring data on both rising and falling edges of clock.
 - 8) 30 NAND Flogh
 - memory cells restrictly increasing estorage density and overcoming some limitations of Flash NAND.